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United States Patent [19]

Grill et al.

[54] DUAL DAMASCENE PROCESSING FOR SEMICONDUCTOR CHIP INTERCONNECTS

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Related U.S. Application Data

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[51] Int. Cl.⁷ H01L 21/4763

[52] **U.S. Cl.** **438/637**; 438/701; 438/638

[58] Field of Search 438/637, 636,

438/700, 701, 702, 638, 640

[56] References Cited

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[11] Patent Number: 6,140,226

[45] **Date of Patent:** Oct. 31, 2000

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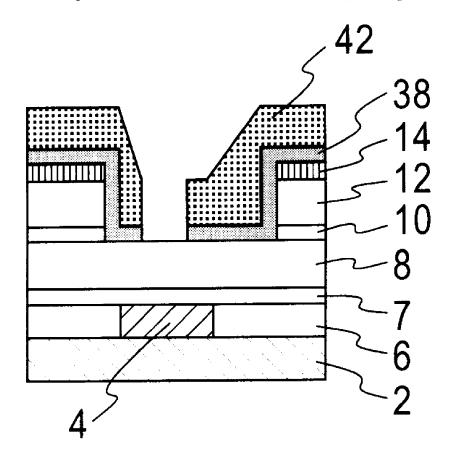
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Primary Examiner—Caridad Everhart Attorney, Agent, or Firm—Robert M. Trepp

[57] ABSTRACT

The present invention relates to lithographic methods for forming a dual relief pattern in a substrate, and the application of such methods to fabricating multilevel interconnect structures in semiconductor chips by a Dual Damascene process in which dual relief cavities formed in a dielectric are filled with conductive material to form the wiring and via levels. The invention comprises a twice patterned single mask layer Dual Damascene process modified by the addition of an easy-to-integrate sidewall liner to protect organic interlevel and intralevel dielectrics from potential damage induced by photoresist stripping steps during lithographic rework. The invention further comprises a method for forming a dual pattern hard mask which may be used to form dual relief cavities for use in Dual Damascene processing, said dual pattern hard mask comprising a first set of one or more layers with a first pattern, and a second set of one or more layers with a second pattern.

48 Claims, 8 Drawing Sheets





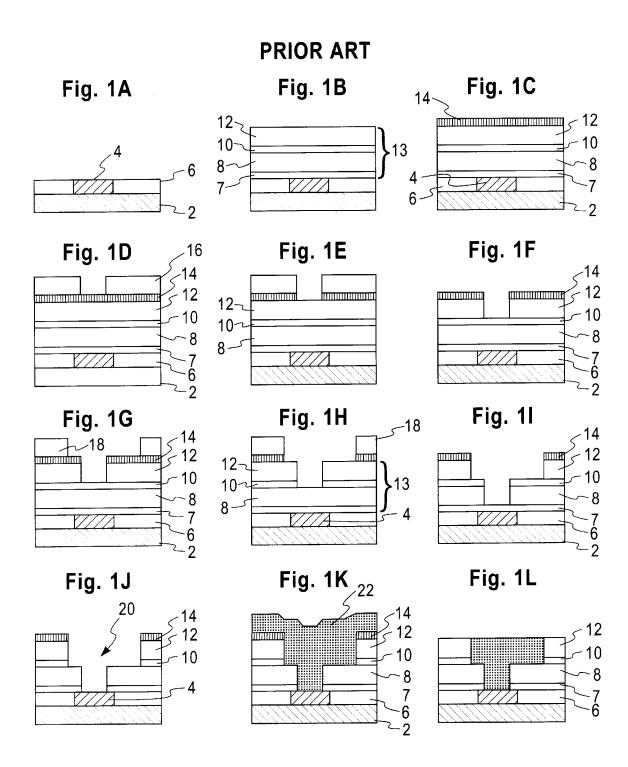


Fig. 2A

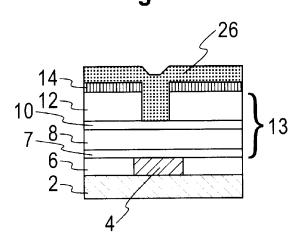


Fig. 2B

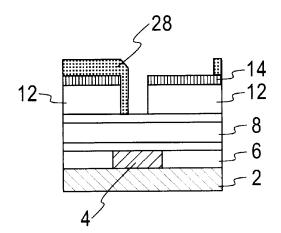


Fig. 2C

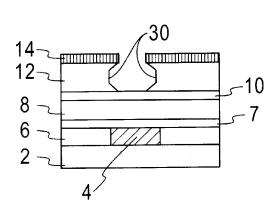
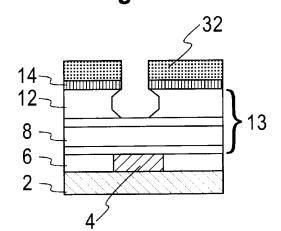


Fig. 2D



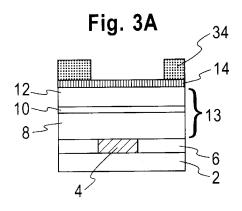
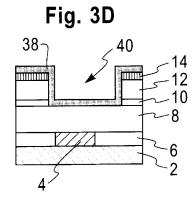
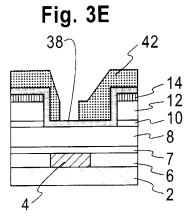


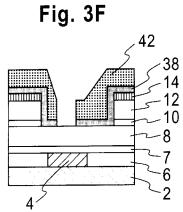
Fig. 3B

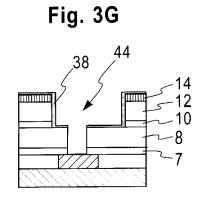
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12
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8

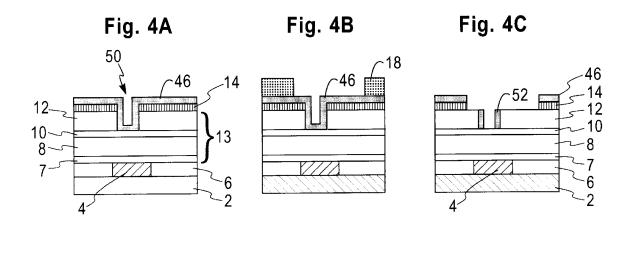
Fig. 3C

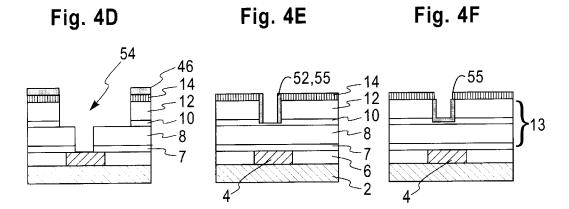












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